Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L9	3	(("C4" or evaporat$4) near2 mask$3).clm. same (smooth$4 or rough$4 or polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/01 17:04
L10	15	(("C4" or evaporat$4) near2 mask$3) near10 (smooth$4 or rough$4 or polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/01 17:05
L11	30	(("C4" or evaporat$4) near2 mask$3) with (smooth$4 or rough$4 or polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/01 17:05
S1	32	((moly or molybdenum or mo) adj2 mask$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 12:24
S2	1	((moly or molybdenum or mo) adj2 mask$3).clm. and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/01 17:03
S3	1	((moly or molybdenum or mo) adj2 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:50
S4	395	(216/12).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:56
S5	44	(moly or molybdenum or mo) and S4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:52
S6	10	S5 and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:46

S7	16	((moly or molybdenum or mo) adj2 mask$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:54
S8	38	((moly or molybdenum or mo) near2 mask$3).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:54
S9	10	((moly or molybdenum or mo) near2 mask$3).clm. and c4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:54
S10	878	(216/83).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:56
S11	427	(216/88).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:56
S12	383	(216/89).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/22 17:56
S13	14	((moly or molybdenum or mo) adj2 mask$3) same (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:37
S14	2	((moly or molybdenum or mo) adj2 mask$3) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	JPO	OR	OFF	2005/04/25 15:38
S15	3	((moly or molybdenum or mo) with (deposit$3 or evaporat$3) with mask$3).clm. and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/04/25 15:41
S16	195	(438/942).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:44

S17	36	(438/943).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:09
S18	174	(438/944).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S19	258	(438/945).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S20	26	(438/946).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S21	240	(438/947).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S22	165	(438/948).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S23	373	(438/949).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S24	135	(438/950).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S25	600	(438/951).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10
S26	167	(438/952).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:10

S27	2122	(S16 or S17 or S18 or S19 or S20 or S21 or S22 or S23 or S24 or S25 or S26)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:11
S28	198	(S16 or S17 or S18 or S19 or S20 or S21 or S22 or S23 or S24 or S25 or S26) and (moly or molybdenum or mo)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:12
S29	64	(S16 or S17 or S18 or S19 or S20 or S21 or S22 or S23 or S24 or S25 or S26) and (moly or molybdenum or mo).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:18
S30	243	(S16 or S17 or S18 or S19 or S20 or S21 or S22 or S23 or S24 or S25 or S26) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:12
S32	52	((moly or molybdenum or mo) near3 mask$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:14
S33	65	((moly or molybdenum or mo) near5 mask$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:13
S34	764	(430/4).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:17
S35	7436	(430/5).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:17
S36	971	(S34 or S35) and (moly or molybdenum or mo)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:27
S37	342	(S34 or S35) and (moly or molybdenum or mo).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:27

S38	68	(S34 or S35) and (moly or molybdenum or mo) and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:28
S40	20	(S34 or S35) and (moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical) and adhesive	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:28
S41	1	("0446879").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:32
S42	2	("4468799").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:32
S44	113	((moly or molybdenum or mo) near3 mask$3) same (polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 13:12
S45	59	((moly or molybdenum or mo) near3 mask$3) and ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical) near3 mask$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:58
S46	44	((moly or molybdenum or mo) near3 (polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)) same mask$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/17 12:59
S47	993	(moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	EPO; JPO; DERWENT	OR	OFF	2005/06/17 13:12
S48	55	(moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical) and (mask$3 or c4 or solder or bump or circuit)	EPO; JPO; DERWENT	OR	OFF	2005/06/17 13:13

S49	92	(moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical) and (mask$3 or c4 or solder or paste or conductive or bump or circuit)	EPO; JPO; DERWENT	OR	OFF	2005/06/17 13:13
S50	129	(moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical) and (mask$3 or c4 or solder or paste or conduct$3 or bump or circuit)	EPO; JPO; DERWENT	OR	OFF	2005/06/17 13:13
S51	1	((moly or molybdenum or mo) near3 mask$3) and ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)) and adhesive$1	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:42
S52	53	((moly or molybdenum or mo) near3 mask$3) with ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:02
S53	3	((moly or molybdenum or mo) with mask$3) and ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)) and adhesive$1	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:02
S54	89	((moly or molybdenum or mo) with mask$3) with ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:09
S55	2881	((evaporat$5 or deposit$5) with mask$3) with ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:10
S56	137	((evaporat$5 or deposit$5) with mask$3) with ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:11
S57	33	((evaporat$5 or deposit$5) near2 mask$3) with ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:11

S58	1	((moly or molybdenum or mo) near5 mask$3) with (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3) with (smoothness or roughness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:14
S59	2	((moly or molybdenum or mo) with mask$3) same (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3) same (smoothness or roughness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:16
S60	12	((moly or molybdenum or mo) with mask$3) same (smoothness or roughness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:19
S61	132	((moly or molybdenum or mo) and mask$3).ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:24
S62	6	("4603056").URPN.	USPAT	OR	OFF	2005/07/12 17:20
S63	6	("3757733" | "3764379" | "4342617" | "4420498" | "4429011").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/12 17:21
S64	6	("3757733" | "3764379" | "4342617" | "4420498" | "4429011").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/12 17:21
S65	26	((screening or (screen adj printing)) near3 mask$3) with (polish$3 or rough$4 or smooth$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:42
S66	1	1997-208100.NRAN.	DERWENT	OR	OFF	2005/07/12 17:26
S67	24	((moly or molybdenum or mo) near3 mask$3) and ((polish$3 or clean$3 or CMP or (chemical adj mechanical) or chemical-mechanical))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/12 17:40
S68	176	((screening or (screen adj printing) or deposition or evaporation) near3 mask$3) with (polish$3 or rough$4 or smooth$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 13:56
S69	1	2003-651457.NRAN.	DERWENT	OR	OFF	2005/07/12 17:50
S70	180	((screening or (screen adj printing) or deposition or evaporation or moly or molybdenum) near3 mask$3) with (polish$3 or rough$4 or smooth$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 13:59

S71	177	((screening or (screen adj printing) or deposition or evaporation) near3 mask$3) with (polish$3 or rough$4 or smooth$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 13:57
S72	3	S70 not S71	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 13:59
S73	580	((screening or (screen adj printing) or deposition or evaporation or moly or molybdenum) with mask$3) with (polish$3 or rough$4 or smooth$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 13:59
S74	403	S73 not S71	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 14:12
S75	2	("4468799").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 14:12
S76	390	((moly or molybdenum or mo) with mask$3) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:21
S77	94	((moly or molybdenum or mo) with (mask$3 or template)) and ((mask or template) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/20 14:14
S78	52	((moly or molybdenum or mo or screen$3) with mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:27
S79	171	((moly or molybdenum or mo or screen$3 or deposition or evaporation) near4 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:31

S80	134	((moly or molybdenum or mo or screen$3 or deposition or evaporation) near3 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:25
S81	91	((moly or molybdenum or mo or screen$3 or deposition or evaporation) near2 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:27
S82	104	((moly or molybdenum or mo or screen$3 or deposition or evaporation or paste) near2 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:31
S83	16	((moly or molybdenum or mo or screen$3) near2 mask$3) with (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:29
S84	22	(moly or molybdenum or mo)and S79	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:30
S85	4	((moly or molybdenum or mo) and (CMP or (chemical adj mechanical) or chemical-mechanical)).ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:33
S86	20	(moly or molybdenum or mo).ti. and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:33
S87	1	(moly or molybdenum or mo).ti. and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:33
S88	11	((moly or molybdenum or mo) with (CMP or (chemical adj mechanical) or chemical-mechanical)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:38

S89	103	((moly or molybdenum or mo) with (CMP or (chemical adj mechanical) or chemical-mechanical))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:37
S90	276	((moly or molybdenum or mo) and (CMP or (chemical adj mechanical) or chemical-mechanical)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:20
S91	24	S89 and S90	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:38
S92	0	(((moly or molybdenum or mo) near3 mask$3) and etch$3 and holes).clm.	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:43
S93	0	(((moly or molybdenum or mo) near3 mask$3) and etch$3 and holes).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:43
S94	131	(((moly or molybdenum or mo) and mask$3) and etch$3 and holes).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:43
S95	8	(((moly or molybdenum or mo) and mask$3) and etch$3 and holes and (polish$3 or rolling or rolled or stoning or stoned)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:45
S96	10	(((moly or molybdenum or mo) with mask$3) and (rolling or rolled or stone or stoning or stoned)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:48
S97	3459	(moly or molybdenum or mo or "c4") with mask$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:48
S98	823	(moly or molybdenum or mo or "c4") near2 mask$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:49

S99	264	S98 and (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3 or stone or stoned or stoning or rolling or rolled or smooth$4 or rough$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:51
S100	649	S98 and (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3 or etch$3 or stone or stoned or stoning or rolling or rolled or smooth$4 or rough$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 15:51
S101	67	((moly or molybdenum or mo) and (metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)) and ((potassium adj hydroxide) or (nitric adj acid)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:29
S102	4	((metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)) and ((potassium adj hydroxide) or (nitric adj acid))	JPO	OR	OFF	2005/07/21 16:23
S103	42	((metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)) and ((potassium adj hydroxide) or (nitric adj acid))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:26
S104	9	((metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)) and ((potassium adj hydroxide))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:27
S105	29	(metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical) and (KOH or (potassium adj hydroxide))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:27
S106	67	(moly or molybdenum or mo) and ((metal or meta$1lic or conduct$3) and (CMP or (chemical adj mechanical) or chemical-mechanical)) and ((potassium adj hydroxide) or (nitric adj acid)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/21 16:30
S107	1	2005-275584.NRAN.	DERWENT	OR	OFF	2005/07/21 16:37

S10 8	89	(adhesive same vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:47
S10 9	53	((adhesive or tape) with vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:48
S11 0	97	((adhesive or tape) same vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:47
S11 1	44	S110 not S109	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:47
S11 2	39	((adhesive or tape) with hole) and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:48
S11 3	38	((adhesive or tape) with (hole$1 or pore$1)) and vacuum and (CMP or (chemical adj mechanical) or chemical-mechanical).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:49
S11 4	1	((adhesive or tape) with (hole$1 or pore$1) with vacuum) same (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:50
S11 5	127	((adhesive or tape) same (hole$1 or pore$1) same vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:51
S11 6	24	((adhesive or tape) same (hole$1 or pore$1) same vacuum) same (CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 12:51
S11 7	28	((adhesive or tape) and (hole$1 or pore$1) and vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3)	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:26

S11 8	8868	((adhesive or tape) and (hole$1 or pore$1) and vacuum) and (CMP or (chemical adj mechanical) or chemical-mechanical or polish$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:27
S11 9	155	(vacuum adj chuck) same (tape or adhesive) same (holes or porous or pores or through-hole$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:31
S12 0	7335	(tape or adhesive) near3 (uv-releas$3 or uv-actrivated or photoreleas$3 or "u.v." or ultraviolet)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:32
S12 1	4697	(tape or adhesive) near2 (uv-releas$3 or uv-actrivated or photoreleas$3 or "u.v." or ultraviolet)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:39
S12 2	2299	S120 and (vacuum or chuck or polish$3 or cmp)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:33
S12 3	304	S120 and (vacuum or chuck) and (polish$3 or cmp)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:33
S12 4	287	(tape or adhesive) near3 (uv$1releas$3 or photoreleas$3 or (releas$3 with uv))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:40
S12 5	105	S124 and vacuum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:44
S12 6	2213	(438/692).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:44
S12 7	809	(438/693).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:45

S12 8	29	(S126 or S127) and ((adhesive or tape) same (hole$1 or pore$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:48
S12 9	778	(vacuum and (chuck or holder) same (adhesive or tape) same (hole$1 or pore$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:50
S13 0	423	(vacuum same (chuck or holder) same (adhesive or tape) same (hole$1 or pore$1))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 13:50
S13 1	344	(vacuum same (chuck or holder) same (adhesive or tape) same (hole$1 or pore$1))	US-PGPUB; USPAT	OR	OFF	2005/07/26 14:09
S13 2	192	(vacuum and (adhesive or tape)) same ((hole$1 or pore$1) near3 (substrate or workpiece))	US-PGPUB; USPAT	OR	OFF	2005/07/26 14:12
S13 3	130	(vacuum same (adhesive or tape)) same ((hole$1 or pore$1) near3 (substrate or workpiece))	US-PGPUB; USPAT	OR	OFF	2005/07/26 14:12
S13 4	765	(430/4).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 14:22
S13 5	7506	(430/5).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 14:22
S13 6	199	(S134 or S135) and (moly or molybdenum or mo) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 14:23
S13 7	145	(S134 or S135) and (adhesive or tape) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 14:29
S13 8	108	(mask$3 with (moly or Mo or molybdenum)) and (adhesive or tape) and (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/26 14:30

S139	14	((moly or molybdenum or mo) adj2 mask$3) same (polish$3 or CMP or (chemical adj mechanical) or chemical-mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 12:15
S140	12	((moly or molybdenum or mo) near3 mask$3) and (polish$3 or CMP or chemical near3 mechanical)	USOCR	OR	OFF	2005/07/29 12:16
S141	9	("2226381" | "2226384" | "3476658" | "3862018" | "4603056" | "4818661").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/07/29 12:21
S142	2	(((moly or molybdenum or mo) near2 mask$3) and (CMP or (chemical near2 mechanical))).clm.	US-PGPUB; USPAT	OR	OFF	2005/07/29 13:25
S143	6	(((moly or molybdenum or mo) near2 mask$3) same (CMP or (chemical near2 mechanical)))	US-PGPUB; USPAT	OR	OFF	2005/07/29 12:26
S144	6	(((moly or molybdenum or mo) near3 mask$3) same (CMP or ((chemical or polish$3) near3 mechanical)))	US-PGPUB; USPAT	OR	OFF	2005/07/29 12:27
S145	13	(((moly or molybdenum or mo) near3 mask$3) same (polish$3 CMP or ((chemical or polish$3) near3 mechanical)))	US-PGPUB; USPAT	OR	OFF	2005/07/29 12:27
S146	39	(((moly or molybdenum or mo) and mask$3) and (polish$3 or CMP or (chemical near3 mechanical)))	EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 12:28
S147	1	(codding near2 steven).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:20
S148	18	(krywanczyk and timothy).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:21
S149	2	(krywanczyk and timothy).in. and molybdenum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:22
S150	5	(danaher and joseph).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:23

S15 1	20	(malinowski near2 john).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:24
S15 2	1	(malinowski near2 john).in. and molybdenum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:23
S15 3	216	(palmer near2 james).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:24
S15 4	2	(palmer near2 james).in. and molybdenum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/07/29 13:24
S15 5	2	(((moly or molybdenum or mo) near2 mask$3) and (polish$3 or CMP or (chemical near2 mechanical))).clm.	US-PGPUB; USPAT	OR	OFF	2005/07/29 13:25
S15 6	20	(((moly or molybdenum or mo) near10 mask$3) and (polish$3 or CMP or (chemical near10 mechanical)))	USOCR	OR	OFF	2005/07/29 13:26
S15 7	1	(((moly or molybdenum or mo) near10 mask$3) near20 (polish$3 or CMP or (chemical near10 mechanical)))	USOCR	OR	OFF	2005/07/29 13:26